

Transaction Information

Tool ID	LKSC759(LKLN759)
Tool Status	Connected
Location	Woodlands, Singapore
Wafer Size	300 mm
Fab Section	Lithography
Tool Available Date	2022-02-23

General Product Information

Vendor Supplier	Nikon
Model	Nikon S208D
Vintage	2006
Serial No	8732034
Asset Description	Nikon MainBody
Software Version	MCSW ver.180-P12/OCSW ver.180-P10
CIM	SECs
Process	Krf

Hardware Configuration (Fab)

System Type	Description	Quantity	Status
Main System	Main Body	1	OK
Handler System	External FOUP System	1	OK
Others			
Options System			
Factory Interface	SMIF	1	OK

Hardware Configuration (Subfab / Auxilliary Units)

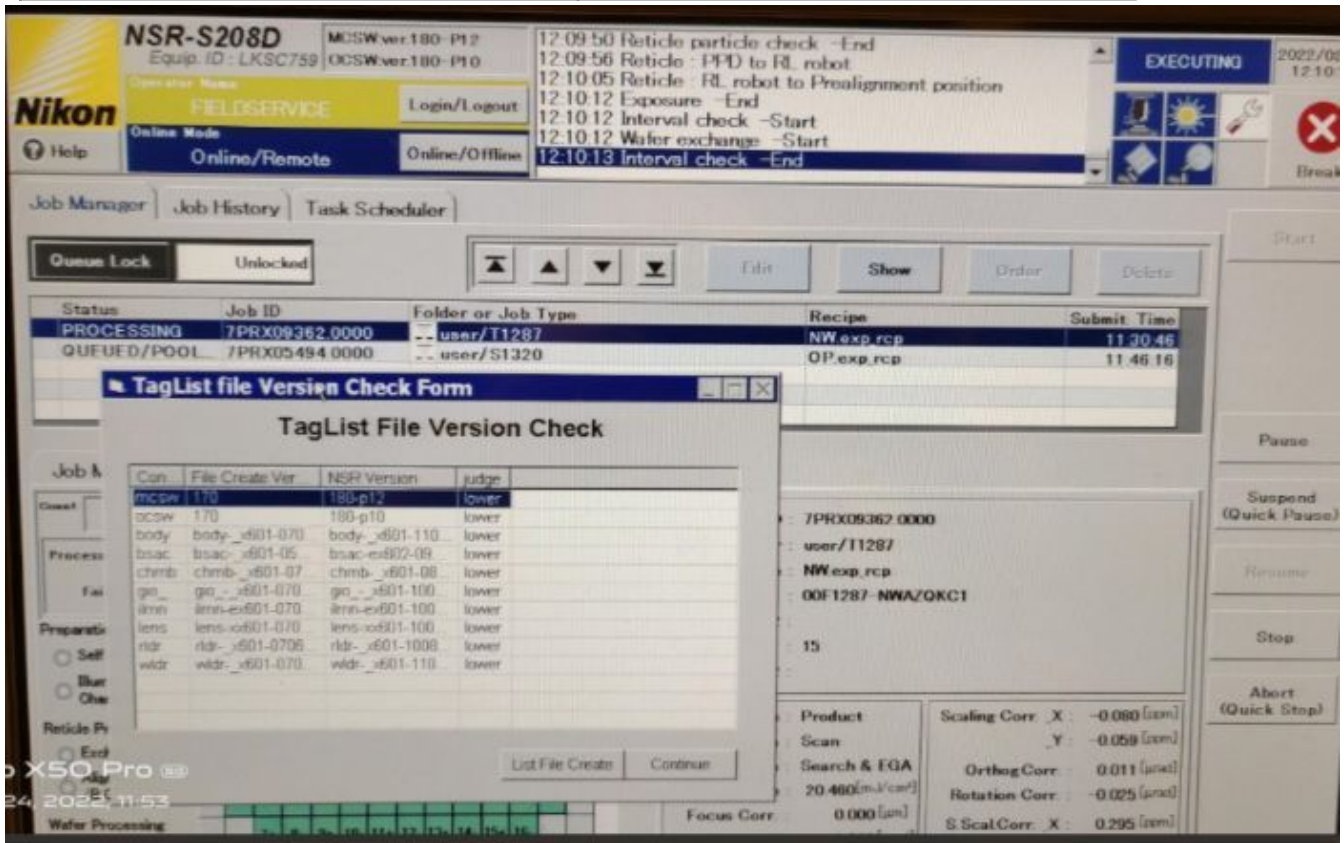
Description	Quantity	Status
Amp Rack	1	OK
Gigaphoton Laser	1	OK
Temperature Controller	1	OK
Air Conditioner	1	OK

Missing/Faulty Parts / Accesories List

Description	Quantity
NA	

Tool Pictures

General Main Body



General

Main Body









Hardware Sub-fab

GigaLaser/AmpRack/
TempController/AirConditioner



Temperature
Controller

Air Conditioner

vivo X50 Pro
Feb 23, 2022, 12:03

Hardware Sub-fab

GigaLaser/AmpRack/
TempController/AirConditioner



Hardware Sub-fab

GigaLaser/AmpRack/
TempController/AirConditioner



Manufacture Serial

Serial No. Plate

CLASS 1 LASER PRODUCT
EN60825-1:1994+A11:1996+A2:2001

クラス1レーザ製品
EN60825-1:1994+A11:1996+A2:2001

LKSC 759
PLIP0074 (F7-LITHO)



GLOBALFOUNDRIES
NIKON 248nm KrF S2 08 scanner (not of
tool layer)
Asset Number: PLIP0074_M(06)
Equipment ID
LKSC759

No.8732034

Additional Tool Data Files

Machine ID:LKNL759			
Reticle Blind		Setting value	44580
XM Outside		400 ~ 800 um	600
XP Inside		400 ~ 800 um	600
YM Outside		400 ~ 800 um	600
YP Inside		400 ~ 800 um	600
Lens performance Data			
Illumination Check		Setting value	44580
ID1	Uniformity	$\leq 0.8 \%$	0.00251
	Power	$> 3000 \text{ mw/cm}^2$	4064
ID13	Uniformity	$\leq 0.8 \%$	0.00212
	Power	$> 3000 \text{ mw/cm}^2$	3572
ID15	Uniformity	$\leq 0.8 \%$	0.00235
	Power	$> 3000 \text{ mw/cm}^2$	3541
ID17	Uniformity	$\leq 0.8 \%$	0.00474
	Power	$> 3000 \text{ mw/cm}^2$	3547
ID21	Uniformity	$\leq 0.8 \%$	0.00315
	Power	$> 3000 \text{ mw/cm}^2$	3944
Wafer Stage Mirror Bow		Setting value	44580
Upper	Sub value X	$\leq 8 \text{ nm}$	0.558
	Sub value Y	$\leq 8 \text{ nm}$	0.573
Lower	Sub value X	$\leq 8 \text{ nm}$	0.55
	Sub value Y	$\leq 8 \text{ nm}$	0.602
Twist	Sub value X	$\leq 8 \text{ nm}$	7.877
	sub value Y	$\leq 8 \text{ nm}$	0.555
		Setting value	44580
Projection Lens Image Plane	Angle X	$0 \pm 1 \text{ urad}$	-0.015
	Angle Y	$0 \pm 3 \text{ urad}$	-0.204
Field Inclination TFD	max - min	$\leq 0.080 \text{ um}$	0.045
	All reading have?	Yes / No	Yes
Flare check(Please inform EE when $E0 \leq 240 \text{mj}$)	E0	$\geq 240 \text{ mj}$	300
Best Focus		$0 \pm 0.015 \text{ um}$	0.0132
Wafer Loader Repeatability (Front)		Setting value	44580
Y 3Sigma		$\leq 15 \text{ um}$	9.653
Rot 3Sigma		$\leq 200 \text{ urad}$	168.497
X 3Sigma		$\leq 15 \text{ um}$	7.239
Rotation Mean		$0 \pm 200 \text{ urad}$	-35.627
Y mean		$0 \pm 10 \text{ um}$	3.075
X mean		$0 \pm 10 \text{ um}$	8.545
FIA Overlay Matching		Setting value	44580

Residual X 3Sigma		< 20nm	14.8
Residual Y 3Sigma		< 20nm	15.2
Plus/Minus Difference X		< 10nm	5.2
Plus/Minus Difference Y		< 10nm	3